

Notice of References Cited	Application/Control No. 10/550,855		Applicant(s)/Patent Under Reexamination VON KAENEL, HANS	
	Examiner Sonya D. McCall-Shepard		Art Unit 2813	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Rosenblad et al., "Low-temperature heteroepitaxy by LEPECVD", Thin Solid Films 318 (1998) pp. 11-14.
	V	Rosenblad et al., "Epitaxial growth at high rates with LEPECVD", Thin Solid Films 336 (1998) pp. 89-91.
	W	Hackbarth et al., "Alternatives to thick MBE-grown relaxed SiGe buffers", Thin Solid Films 369 (2000) pp. 148-151.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.